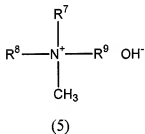
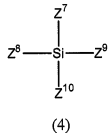
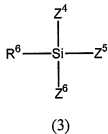
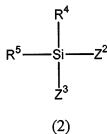
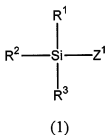


Amendments to the Claims:

1. (Currently amended) A composition for forming a porous film, the composition comprising a hydrolysis and condensation product of an alkoxysilane or a partial hydrolysis product of the alkoxysilane in an organic solvent in the presence of trialkylmethylammonium hydroxide as a catalyst, wherein the trialkylmethylammonium hydroxide comprises a reaction product of trialkylamine and dimethyl carbonate, and wherein the alkoxysilane comprises one or more alkoxysilanes selected from the groups consisting of compounds represented by formulae (1) to (4) below, and the trialkylmethylammonium hydroxide is represented by formula (5) below,



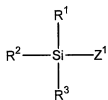
wherein $\text{Z}^1, \text{Z}^2, \text{Z}^3, \text{Z}^4, \text{Z}^5, \text{Z}^6, \text{Z}^7, \text{Z}^8, \text{Z}^9$ and Z^{10} each independently represents an alkoxy group having 1 to 6 carbons; $\text{R}^1, \text{R}^2, \text{R}^3, \text{R}^4, \text{R}^5$ and R^6 each independently represents a monovalent hydrocarbon group which is optionally substituted; and R^7, R^8 and R^9 each independently represents an alkyl group having 1 to 6 carbons,
 wherein the composition comprises 10 ppm or less halogen impurity and 100 ppb or less metallic impurity wherein boron is counted in the metallic impurity.

2. (Previously Presented) The composition for forming a porous film according to Claim 1 wherein the total carbon number of R^7 , R^8 and R^9 in said trialkylmethylammonium hydroxide is 4 to 15.

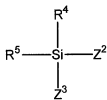
3. (Cancelled)

4. (Previously Presented) The composition for forming a porous film according to Claim 1, wherein said hydrolysis and condensation product of an alkoxysilane or the partial hydrolysis product of the alkoxysilane comprises a product having a weight-average molecular weight of 10,000 to 1,000,000.

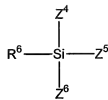
5. (Previously Presented) A method for manufacturing a composition for forming a porous film, comprising hydrolysing and condensing an alkoxysilane or a partial hydrolysis product of the alkoxysilane in an organic solvent in the presence of trialkylmethylammonium hydroxide as a catalyst, wherein the alkoxysilane comprises one or more alkoxysilanes selected from the group consisting of compounds represented by formulae (1) to (4) below, and the trialkylmethylammonium hydroxide is represented by formula (5) below which is a reaction product of trialkylamine and dimethyl carbonate,



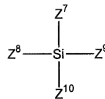
(1)



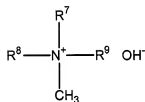
(2)



(3)



(4)



(5)

wherein $\text{Z}^1, \text{Z}^2, \text{Z}^3, \text{Z}^4, \text{Z}^5, \text{Z}^6, \text{Z}^7, \text{Z}^8, \text{Z}^9$ and Z^{10} each independently represents an alkoxy group having 1 to 6 carbons; $\text{R}^1, \text{R}^2, \text{R}^3, \text{R}^4, \text{R}^5$ and R^6 each independently represents a monovalent hydrocarbon group which is optionally substituted; and R^7, R^8 and R^9 each independently represents an alkyl group having 1 to 6 carbons.

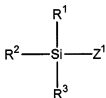
6. (Previously Presented) A method for manufacturing a porous film comprising applying a composition according to Claim 1 to a substrate to form a film thereon, drying the film and heating the dried film to produce a porous film.

7. (Previously Presented) A porous film comprising a composition according to Claim 1.

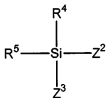
8. (Previously Presented) An interlevel insulating film comprising a composition according to Claim 1.

9. (Currently amended) A semiconductor device comprising a porous film therein, the porous film formed of a composition comprising 10 ppm or less halogen impurity and 100

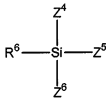
ppb or less metallic impurity where boron is counted in the metallic impurity, the composition comprising the hydrolysis and condensation product of an alkoxyasilane or a partial hydrolysis product of the alkoxyasilane in an organic solvent in the presence of trialkylmethylammonium hydroxide as a catalyst, wherein the trialkylmethylammonium hydroxide comprises a reaction product of trialkylamine and dimethyl carbonate, and wherein the alkoxyasilane comprises one or more alkoxyasilanes selected from the group consisting of compounds represented by formulae (1) to (4) below, and the trialkylmethylammonium hydroxide is represented by formula (5)



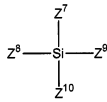
(1)



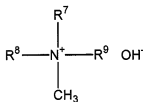
(2)



(3)



(4)



(5)

below,

wherein $\text{Z}^1, \text{Z}^2, \text{Z}^3, \text{Z}^4, \text{Z}^5, \text{Z}^6, \text{Z}^7, \text{Z}^8, \text{Z}^9$ and Z^{10} each independently represents an alkoxy group having 1 to 6 carbons; $\text{R}^1, \text{R}^2, \text{R}^3, \text{R}^4, \text{R}^5$ and R^6 each independently represents a monovalent hydrocarbon group which is optionally substituted; and R^7, R^8 and R^9 each independently represents an alkyl group having 1 to 6 carbons.

10. (Previously Presented) The semiconductor device according to Claim 9 wherein the total carbon number of R^7, R^8 and R^9 in said trialkylmethylammonium hydroxide is 4 to 15.

11. (Cancelled)
12. (Previously Presented) The semiconductor device according to Claim 9 wherein said hydrolysis and condensation product of an alkoxysilane or the partial hydrolysis product of the alkoxysilane comprises a product having a weight-average molecular weight of 10,000 to 1,000,000.
13. (Previously Presented) The semiconductor device according to Claim 9 wherein said porous film is between metal interconnections in a same layer or multi-level interconnects, or is between upper and lower metal interconnection layers.